

Iron in crystalline silicon solar cells: fundamental properties, detection techniques, and gettering

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Outline

- Origins of Fe in multicrystalline Si ingots
- Chemical states and recombination activity of Fe in silicon
- Measuring [Fe_i] by QSSPC and PL imaging
- Gettering of Fe during ingot growth and cell fabrication:
 - Internal gettering at GBs, dislocations and within grains
 - External gettering by P, AI and B diffusions



Origins of Fe in multicrystalline Si ingots

- One of the most common metal contaminants
- **Total** Fe concentration, measured by NAA before and after P gettering
- Comes from the crucible, not the feedstock
- Typically between
 10¹² -10¹⁵ cm⁻³



Macdonald et al. 29th IEEE PVSC New Orleans (2002)



Origins of Fe in multicrystalline Si ingots

- Concentration increases towards top - segregation
- Also increases at bottom solid-state diffusion from crucible
- Only a small fraction is interstitial - around 1%
- Remainder is precipitated (or substitutional)
- The dissolved fraction has a much larger impact on lifetime



Macdonald et al. J. Appl. Phys. 97 033523 (2005)



Recombination activity of interstitial Fe in silicon

- Interstitial Fe (Fe_i) introduces a deep donor level
- Positively charged in p-type Si mobile at RT forms pairs with ionised acceptors.
- Two FeB levels acceptor and donor
- Pairs break under illumination only Fe_i present in working cells



Courtesy of J. Schmidt, ISFH

conduction band

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Recombination activity of Fe in p-type silicon

- Different energy levels and capture cross sections different lifetime curves
- SRH modelling on left, QSSPC data on right (trapping restricts range)





Detecting Fe_i using FeB pairing

 Manipulating the SRH equations shows that:

$$[Fe_i] = C \times \left(\frac{1}{\tau_{Fe_i}} - \frac{1}{\tau_{FeB}}\right)$$

- Zoth and Bergholz developed a famous method based on SPV
- Extended to other methods (uW-PCD and QSSPC)
- Very sensitive (similar to DLTS)
- Only works in p-Si
- Must avoid the crossover point





Detecting Fe_i using FeB pairing

$$[Fe_i] = C \times \left(\frac{1}{\tau_{Fe_i}} - \frac{1}{\tau_{FeB}}\right)$$

- Pre-factor *C* is a function of doping and excess carrier density.
- In true low injection, C becomes constant – ideal measurement region.
- Not accessible to QSSPC or uW-PCD (trapping effects).





Iron imaging with photoluminescence (PL)

- Band-to-band PL imaging rapid and highly-resolved method for low-injection lifetime imaging – no trapping effects.
- Allows low-injection Fe imaging similar to original SPV technique
- Two PL images required, before and after breaking FeB pairs.





Macdonald et al. J. Appl. Phys. 103, 073710 (2008)



Recombination activity of Fe in n-type silicon

- Neutral charge state in n-type less attractive for minority carriers compared to p-type.
- Higher lifetime in n-type in low- to mid-injection.
- Possible incentive for using n-type substrates...





Fe images on mc-Si

- Wafer 20% from bottom of ingot
- High [Fe_i] (10¹³ cm⁻³)
- Internal gettering of Fe during ingot cooling at GBs, dislocation clusters



Liu et al. Progress in PV, 19 649 (2011)



Fe images on mc-Si

- Wafer from near very bottom of ingot
- Moderate [Fe_i] (10¹² cm⁻³)
- Small grains
- Fewer dislocation clusters
- Lower [Fe_i] *within* grains

 presence of
 precipitation sites





Fe images on mc-Si

- Wafer from middle of ingot
- Low [Fe_i] (10¹¹ cm⁻³)
- Reduced gettering at GBs (due to precipitation starting at lower T)





Internal gettering of Fe at GBs during ingot cooling

- Line-scans of PL images with resolution of 25 microns
- 1D diffusion/capture model 2 free parameters diffusion length of Fe_i $L_D(Fe_i)$ and precipitation velocity *P* of the GB
- Have to take care of PL artifacts!
 - Image smearing in the CCD camera use point-spread function de-convolution
 - Carrier spreading in the sample use low-lifetime i.e. high [Fe_i] samples)



Internal gettering of Fe at GBs during ingot cooling

- Same GB on different wafers reveals diffusion length of $Fe_i L_D(Fe_i)$ depends on initial $[Fe_i]$
- Lower [Fe_i] means that precipitation begins later during cooling

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 Modelling ingot cooling time reveals data can only be explained if precipitation at GBs commences after super-saturation ratio of about 50 is reached!





- Annealing at low temps can drive further precipitation at GBs, and within grains.
- Higher temperatures tend to homogenise the dissolved Fe





- At 600 °C, [Fe_i] is far above solubility limit:
 - Strong super-saturation
 - Drives precipitation at GBs, and within grains
- At 800 °C, [Fe_i] is approx equal to the solubility limit:
 - No precipitation
- At 900 °C and above, [Fe_i] is below solubility limit:
 - No precipitation
 - Homogenization by diffusion
 - Dissolution of precipitates also possible





- 500 C annealing for various times
- 1D diffusion/capture model:
 - Widening denuded zone
 - Reduced intra-grain [Fe_i]





- At fixed temp annealing, diffusion length of Fe can be calculated from literature values.
- Very good agreement with fitted values (500 °C)
- A method to measure diffusivity?





Internal gettering of Fe within the grains

- After homogenization on left, after 14 hour anneal at 500 °C on right.
- Precipitation rate varies from grain to grain.





Internal gettering of Fe within the grains

• Precipitation rate varies despite initial Fe concentrations being similar





Internal gettering of Fe within the grains



- Less Fe precipitation in grains of low dislocation density
- Average distance between dislocations is less than Fe diffusion length
- Dislocations act as nucleation sites for Fe precipitation within grains



External gettering of Fe_i by P, AI and B diffusions

• Fe-implanted, annealed, mono FZ p-Si, detected by QSSPC.





Phosphorus gettering of Fe_i

- P gettering removes between 90-99% of Fe better at lower temp
- Adding a post-getter anneal improves gettering further segregation ratio improves



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Phosphorus gettering of Fe_i

- Driving in P diffusion reduces gettering effectiveness
 - Very heavily doped region (>10²⁰ cm⁻³) required for best gettering



Phang and Macdonald, IEEE JPV accepted



Aluminium gettering of Fe_i

- Al gettering removes more than 99.9%!
- However, typical BSF firing is too short for AI gettering to rear side...



Phang and Macdonald, JAP 109, 073521 2011



Boron gettering of Fe_i

- B gettering very effective if Boron Rich Layer (BRL) is present.
- However, BRL is oxidised *in-situ* to allow low J_{oe} re-injects Fe into base.
- Even a low temp anneal does not help much...





Boron gettering of Fe_i

- One solution is to remove the BRL at low temp by etch-back
 - Preserves gettering
 - Allows lower J_{oe}





Boron gettering of Fe_i

- Another idea is to overlay a light phosphorus diffusion 'buried emitter'.
- Gives very good gettering





Conclusions

- Fe is common in mc-Si wafers, both dissolved and precipitated
- Dissolved iron more active in p-type than n-type due to charge state
- QSSPC allows very sensitive [Fe_i] measurements
- PL allows spatially resolved Fe imaging
- Gettering of dissolved Fe is critical for mc-Si cells
 - Internal gettering at GBs, dislocations and in intra-grain regions
 - Strong super-saturation required
 - External gettering via P, B or Al diffusions can be very effective
 - Al and B more effective than P
 - However, B diffusions require the presence of a BRL

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